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APPLICATION NO.	FILING DATE		FIRST NAMED INVENTOR	· · · · · · · · · · · · · · · · · · ·	ATTORNEY DOCKET NO.		
08/900,0	07/	24/97 YEN		` T			
			7	EXAMINER			
			B2M1/0224				
DAVID J.	DAVID J. SIMONELLI			WALLACE,V			
BLISS MO	CGLYNN			ART UNIT	PAPER NUMBER		
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Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks



	08/900,047	Yen			
Office Action Summary	Examiner Valencia Martin Wallace		Group Art Unit 2503		
☐ Responsive to communication(s) filed on <u>Jan 9, 1998</u>				·	
☑ This action is FINAL.					
☐ Since this application is in condition for allowance exce in accordance with the practice under <i>Ex parte Quayle</i>	*		ion as to the me	rits is closed	
A shortened statutory period for response to this action is is longer, from the mailing date of this communication. Frapplication to become abandoned. (35 U.S.C. § 133). Example 27 CFR 1.136(a).	ailure to respond with	in the perio	od for response	will cause the	
Disposition of Claims					
	is/are	is/are pending in the application.			
Of the above, claim(s)		is/are v	withdrawn from	consideration.	
☐ Claim(s)		is/are allowed.			
X Claim(s) 2-6 and 8-17		is/are rejected.			
Claim(s)		is/are objected t	0.		
☐ Claims	are subject	t to restric	tion or election	requirement.	
☐ See the attached Notice of Draftsperson's Patent D. ☐ The drawing(s) filed on is/are ☐ The proposed drawing correction, filed on ☐ The specification is objected to by the Examiner.	objected to by the Ex	aminer.	⊡disappro∨ed.		
☐ The oath or declaration is objected to by the Examin	ner.				
Priority under 35 U.S.C. § 119 Acknowledgement is made of a claim for foreign properties. In received. In received in Application No. (Series Code/Series). Preceived in this national stage application from *Certified copies not received: Acknowledgement is made of a claim for domestic.	pies of the priority do al Number) m the International Bu	cuments ha	ave been Rule 17.2(a)).	·	
Attachment(s) Notice of References Cited, PTO-892 Information Disclosure Statement(s), PTO-1449, Pa Interview Summary, PTO-413 Notice of Draftsperson's Patent Drawing Review, P	-				



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DETAILED ACTION

Claim Rejections - 35 USC § 112

Claims 4-6 and 10-12 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claims 4-6 and 10-12 recite the limitation "said electrically conducting plug". There is insufficient antecedent basis for this limitation in the claims.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless --

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371© of this title before the invention thereof by the applicant for patent.

Claims 3-6 and 9-14, 16 and 17 are rejected under 35 U.S.C. 102(e) as being anticipated by Chappell et al. (U.S. Patent No. 5,541,427).

Chappell et al. disclose a semiconductor structure and a method of forming a local interconnect in a semiconductor structure, comprising:

a silicon substrate (10) having a top surface;



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a diffusion region (43) formed in said substrate adjacent to said top surface;

a polysilicon gate (18) formed on the top surface of said substrate juxtaposed to but not contacting said diffusion region;

a sidewall spacer (28) adjacent to said polysilicon gate and disposed above said diffusion region;

an insulator layer (36) substantially covering said polysilicon gate and said diffusion region; and

a conducting plug (44a) at least partially filling a via in said insulation layer that exposes said sidewall spacer in the absence of said conducting plug, said conducting plug providing direct electrical communication between said polysilicon gate and said diffusion region. Note Chappell et al. Figure 8.

In re claims 3 and 9, said insulator layer is formed of a material such as silicon oxide (see Chappell et al. column 4, lines 23 and 24).

In re claims 4-6 and 10-12, said conducting plug is a metal plug formed of a refractory material such as tungsten (see Chappell et al. column 4, lines 66 and 67).

In re claim 16, said polysilicon gate and said diffusion region are exposed in said via in the absence of said conducting plug (see Chappell et al. Figure 5).

Therefore, Chappell et al. meet and anticipate the claims.



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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 2, 8 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chappell et al. in view of Jones, Jr. (U.S. Patent No. 5,313,089), of record.

The disclosure of Chappell et al. as discussed above. However, Chappell et al. fail to disclose forming the conductive plug with both a refractory metal layer and a layer of glue.

Therefore, to provide the device of Chappell et al. with a conductive plug comprised of an outer glue layer and a plug of a refractory metal as taught by Jones, Jr. would have been obvious to one of ordinary skill in this art because Jones, Jr. specifically teaches the process of forming a semiconductor device similar in structure and function to that of Chappell et al. having a conductive plug (32) within a dielectric layer (30) wherein said plug has a layer of glue and a plug of tungsten, as well known and commonly used in conductive plug technology (see Jones, Jr. column 3, lines 64-68 and column 4, lines 1-17). Note Jones, Jr. Figure 2.

Also, it is obvious that the diffusion regions of Chappell et al. would be of N or P type conductivity because Chappell et al. specify that the regions are. Further, Jones, Jr. specify that the diffusion regions (16, 18) are heavily doped with an impurity (see Jones, Jr. column 3, lines 23-24).



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